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Advances in X-Ray/EUV Optics and Components V

**Shunji Goto
Ali M. Khounsary
Christian Morawe**
Editors

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Introduction

This volume contains papers presented at the conference on "Advances in X-Ray/EUV Optics and Components V", held in San Diego, California, USA, on 2–3, August 2010, as part of the SPIE 2010 International Symposium on Optics + Photonics.

The conference was in six sessions covering "X-ray Optics and Applications," "VUV, SX Optics, and Applications," "Multilayers and Applications," "Mirrors, Zone Plates, and Applications," "X-ray Sources and Detectors," and "Optics and Beam Coherence." It was complemented by a poster session and by other conferences in the X-Ray, Gamma-Ray, and Particle Technologies program track, i.e. on metrology and adaptive x-ray optics.

This conference focused on technological developments in X-ray/EUV optics in astronomy, laser physics, and synchrotron beamline design. Accordingly, the applications covered the spectral range from vacuum ultra violet (VUV) to hard x-rays. Topics related to metrology were presented in the above-mentioned metrology conferences.

This was a very fruitful conference and we would like to thank the authors, speakers, session chairs, program committee members, conference participants, and SPIE staff for their help in making it a success.

Shunji Goto
Ali M. Khounsary
Christian Morawe